

Abstract

DEVICE AND METHOD FOR EXPOSING A LIGHT-SENSITIVE
LAYER TO LIGHT

The present invention relates to a method for exposing a light-sensitive layer (9) to light using an optical system (8), wherein at least one light beam (6, 6') is generated by respectively at least one light source (7) and pixels (23) of an exposure pattern grid (24, 24', 24'', 24''') are illuminated by at least one micro-mirror device (1) with a plurality of micro-mirrors (3), characterised in that an, in particular affine distortion takes place, in particular a shearing, of the exposure pattern grid (24, 24', 24'', 24''').

Figure 1